Correcting the Polygon Feature Pattern with an Optical Proximity Correction Method

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ABSTRACT OF THE INVENTION

The present invention is provided a method to use a pattern section without extra serif to correct the polygon feature pattern with
10 at least one inner corner. Such that the polygon feature pattern with at least one inner corner can achieve effectively OPC (optical proximity correction) without adding any extra data point. Therefore, the present invention can instead of the conventional serif and achieves the effective OPC. In addition, the mask writing time is also improved
15 since the original feature pattern is divided into a few rectangular-shaped mask writing units or trapeze-shaped mask writing units for regular mask writing, and the inner corner is/are not in the middle of each divided mask writing units. The mask inspection is also simplified and easier to calibration since a simple geometry other
20 than complex serif is used.